



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Stefan Peter Hau-Riege

Docket No.: IL-11154

Serial No.:

10/783,520

Group Art Unit: 2877

Filed:

February 20, 2004

Examiner: S. Nguyen

For

: Method For Characterizing Mask Defects Using

Image Reconstruction From X-Ray Diffraction Patterns

<u>AMENDMENT</u>

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed June 26, 2006, please amend the above-referenced application as follows: